Coating characteristics of CYTOP

Example of spin coating (CTX-809A type, CTL-800A type)

1. Coating conditions
   - Spin condition: 500 rpm x 5 sec. -> Specified number of revolution x 20 sec.
   - Baking condition: 180 to 200°C x 30 to 60 min.
   - Substrate: Silicon wafer (150mm in diameter (6 inches))
   - Membrane thickness measurement: ULVAC “DEKTAK”

2. Diagram showing relation between spinning speed and membrane thickness after drying

Example of dip coating (CTX-100AE type, CTL-100AE type)

1. Coating conditions
   - Membrane thickness measurement: ULVAC “DEKTAK”

Precautions for handling

Please be sure to read MSDS before using this product to ensure safe handling.